



Title: "Purging Gas from a Photolithography Enclosure Between a Mask Protective Device and a Pattern Mask"

Inventors: Han-Ming Wu et al. Application No.: 09/752,938 Docket No.: 42P10058

Blakely, Sokoloff, Taylor & Zafman 303-740-1980

1/7

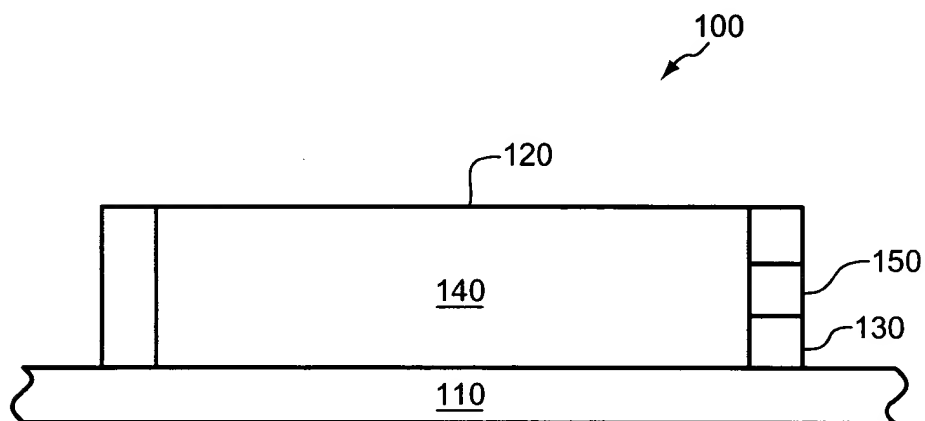


FIG. 1
PRIOR ART



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2/7

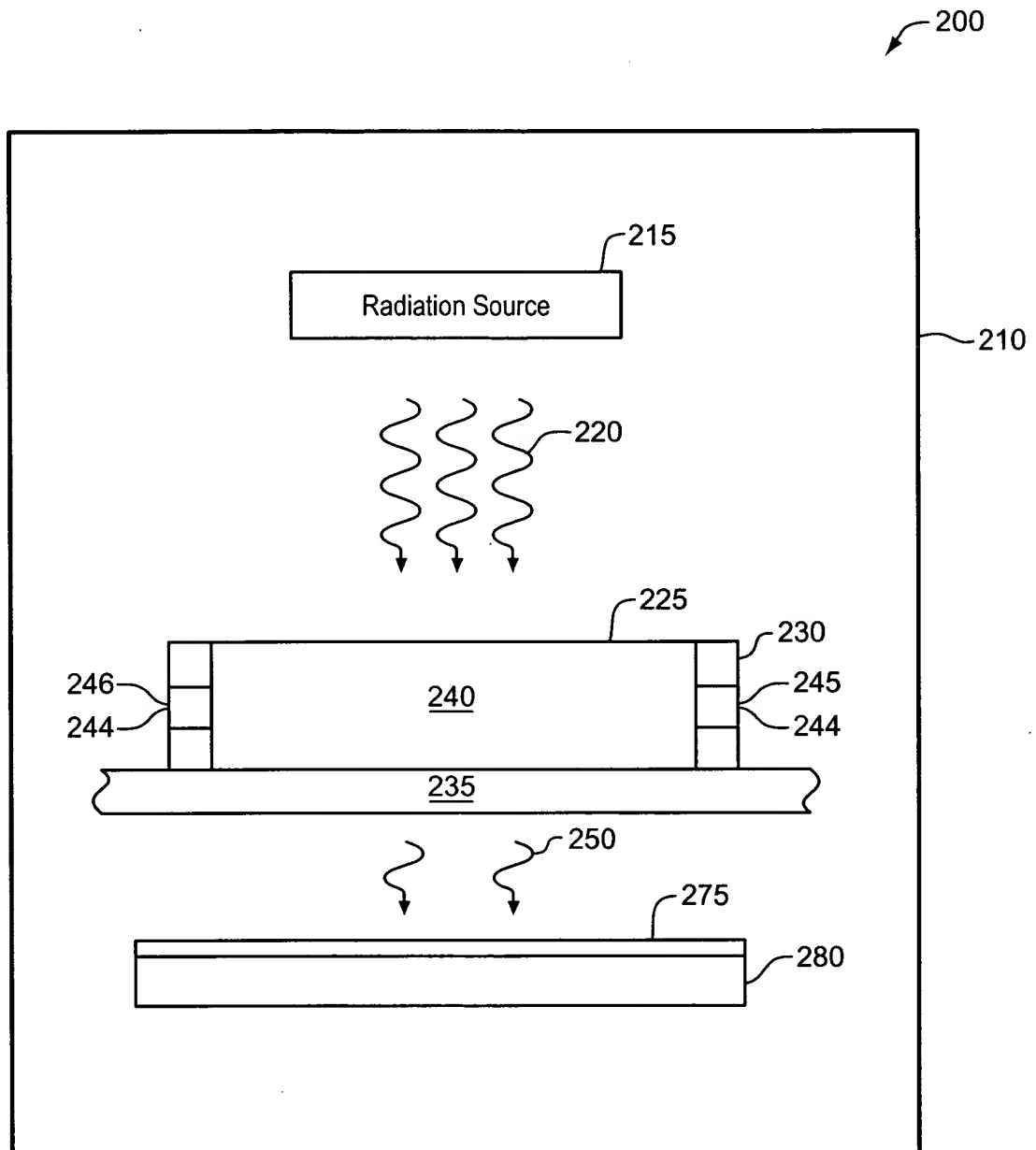


FIG. 2



3/7

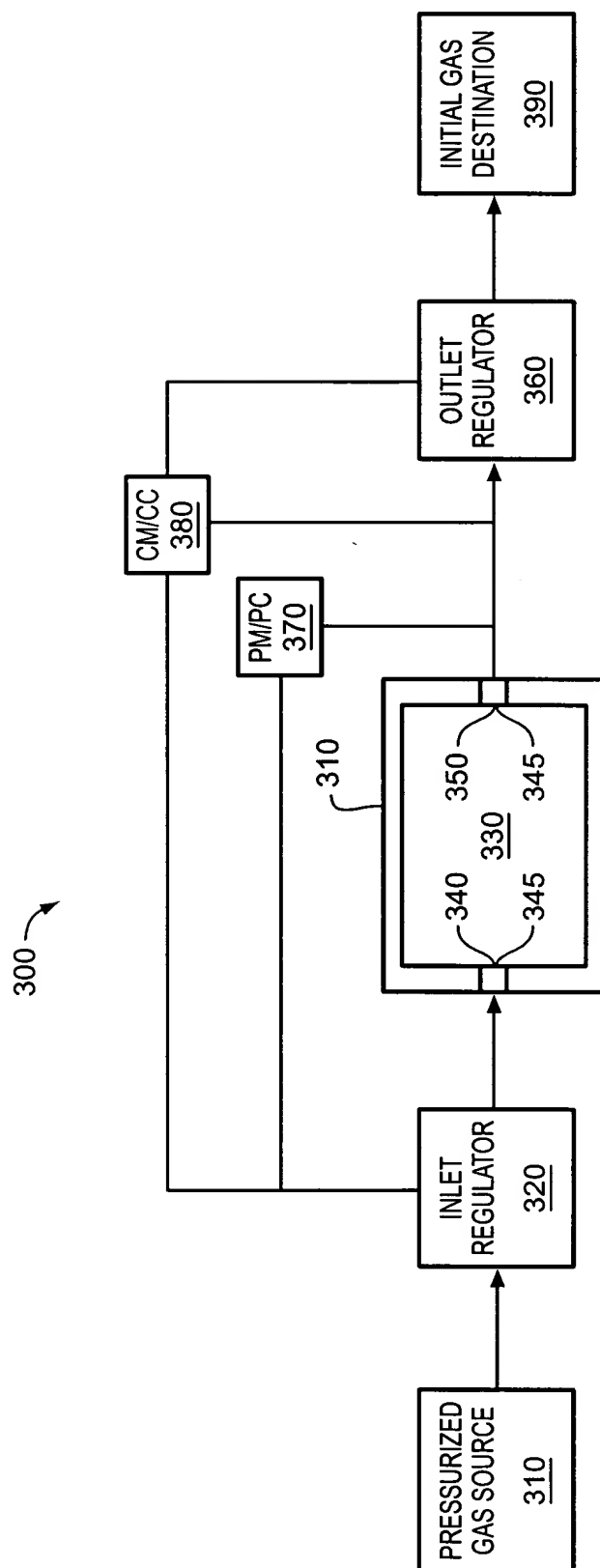


FIG. 3



4/7

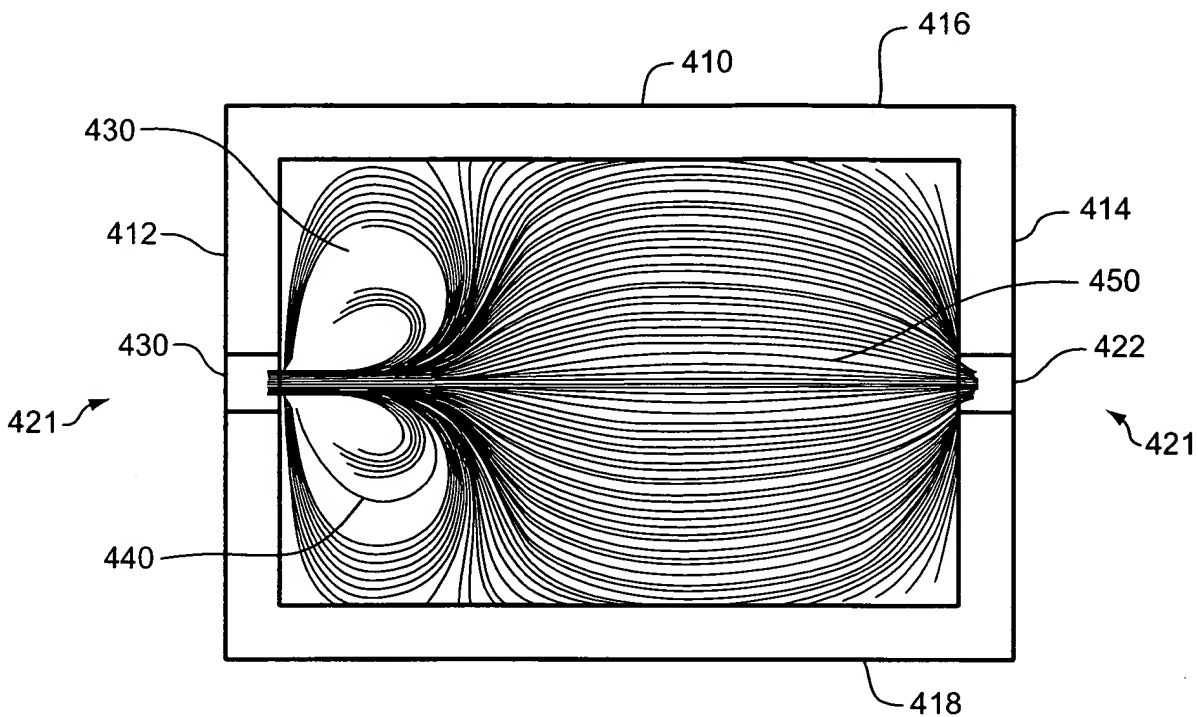
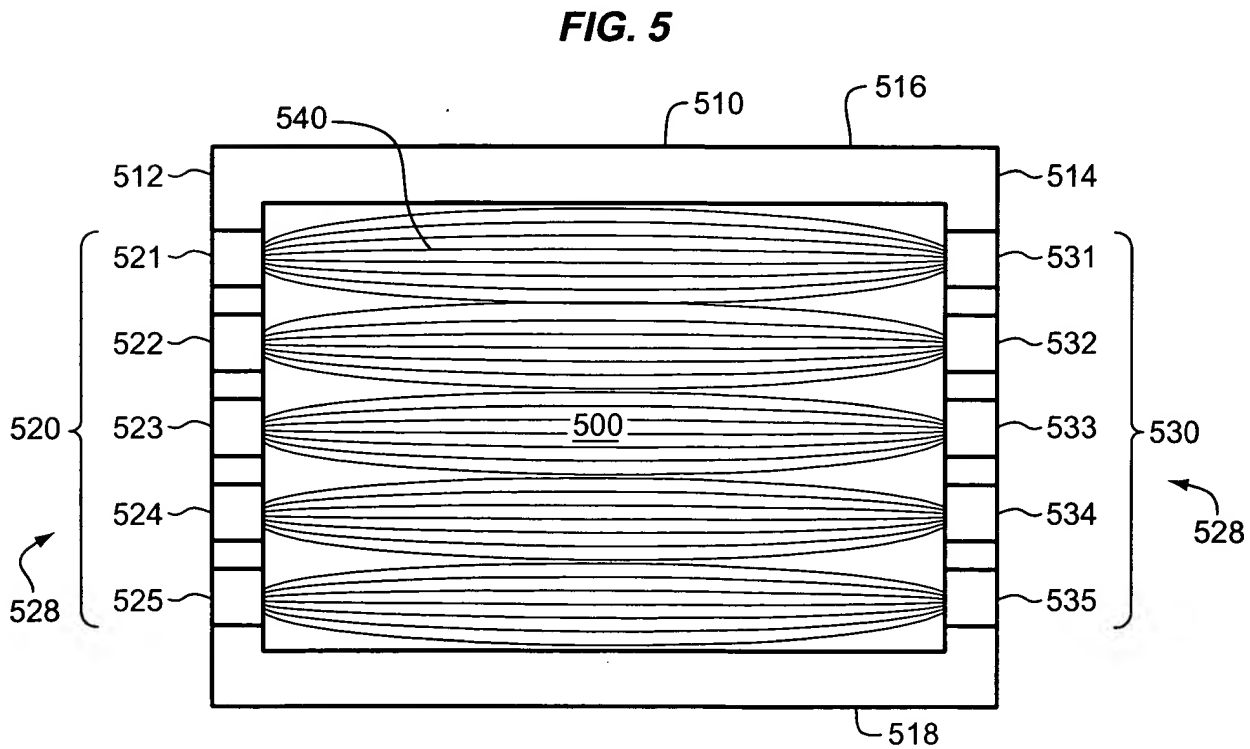


FIG. 4





5/7

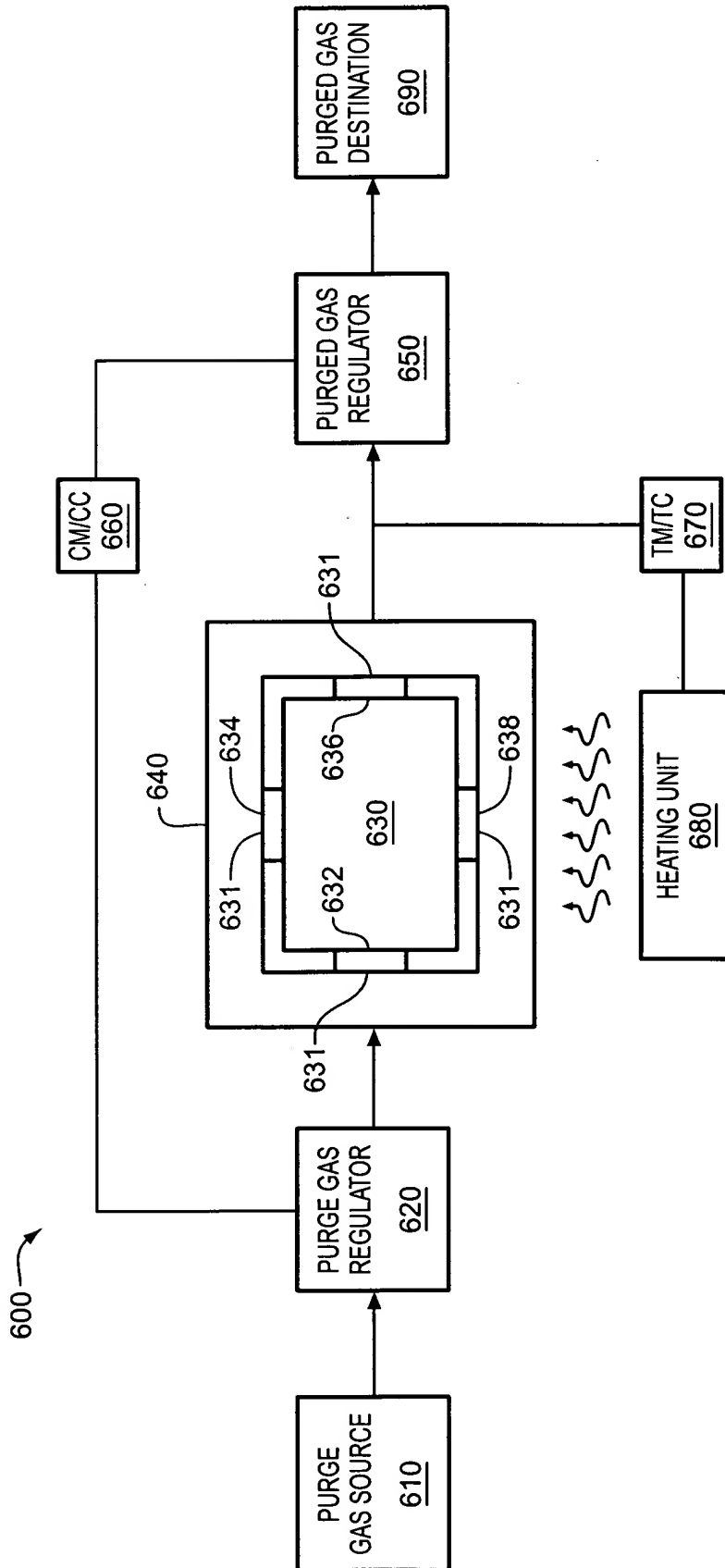


FIG. 6

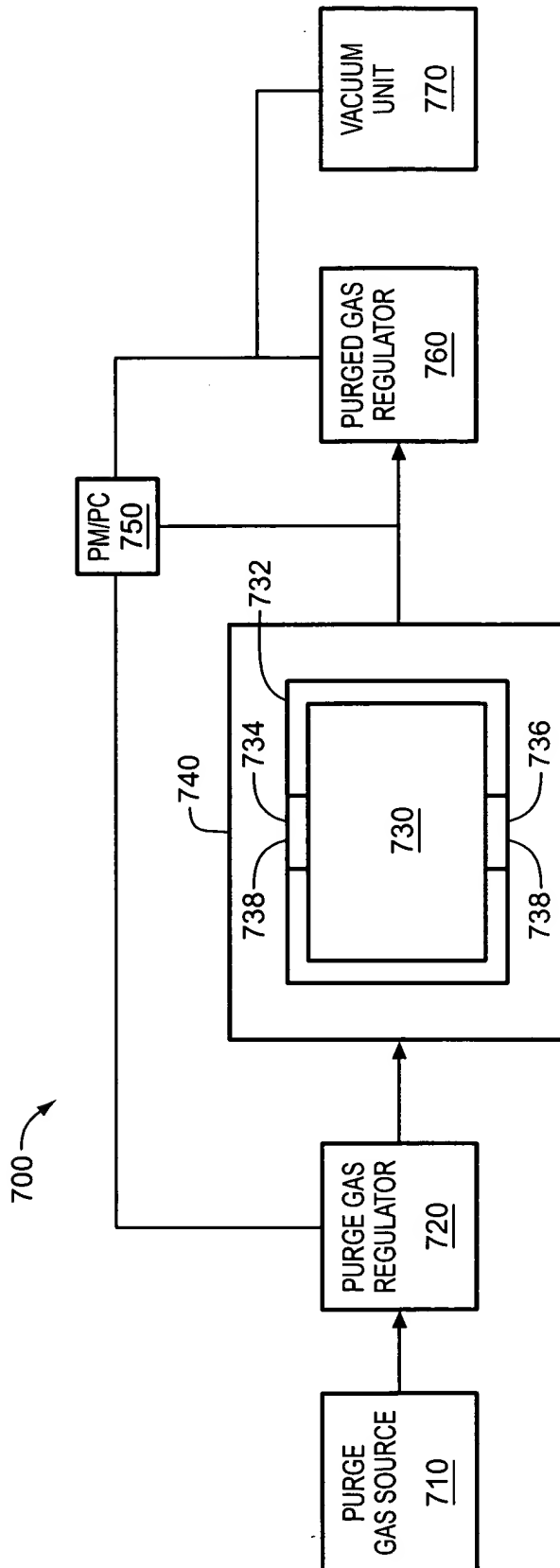


FIG. 7



FIG. 8

